	Hits	Search Text	DBs
26	0	((substrate or wafer or device or workpiece) same (support$3 or stage or hold$3 or pedestal) same (resist or photoresist or photocur$4) same (irradiat$4 or illuminat$4 or (UV near9 source) or excimer or KrF or ArF or e$3beam or (electron near4 beam) or EUV or DUV or VUV or laser)) and pattern$3 and (((pattern$6 near5 device) or mask$4 or reticle) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon) same ((nitrogen or N$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
27	0	(((pattern$6 near5 device) or mask$4 or reticle) same (project$4) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon) same ((nitrogen or N$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
28	3	(((pattern$6 near5 device) or mask$4 or reticle) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or alkyl) same ((nitrogen or N$2) near12 (oxygen or oxide)))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
29	39	(((pattern$6 near5 device) or mask$4 or reticle) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or alkyl or fluoromethane) same ((nitr$4 near6 (oxygen or oxide)) or NO$3))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
30	5	(((pattern$6 near5 device) or mask$4 or reticle) same ($4lithograph$6 or photolithograph$6) same (laser or irradiat$4 or (ion near9 beam)) same ((organic near9 compound) or fluoroalkanes or alkane or hydrocarbon or methane or ethane or methyl or ethyl or (halogen$4 near9 alkane$3) or alkyl or fluoromethane or CF$4) same ((nitr$4 near6 (oxygen or oxide))))	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	72	(projection near9 (optical or $5lithograph$4) near9 (system or apparatus)) and ((radiation or light or optical or laser or project$4 or $4lithograph$6) same (source or system or apparatus)) and ((substrate or wafer or device or workpiece) same (support$3 or stage or hold$3)) and pattern$4 and ((plasma or e$3beam or (electron near4 beam) or beam or RF or (electro$3magnetic near6 field) or (plasma near5 source) or EUV or DUV)) and ((pattern$6 near5 device) or mask$4 or reticle or photo$4mask) and (gas$3 same (plasma or ion$3beam or beam or laser or ion$4assist$5) same (((nitrogen or nitrous or nitric) near16 (oxide or dioxide)) or "NO.sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	72	S31 NOT S29	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB